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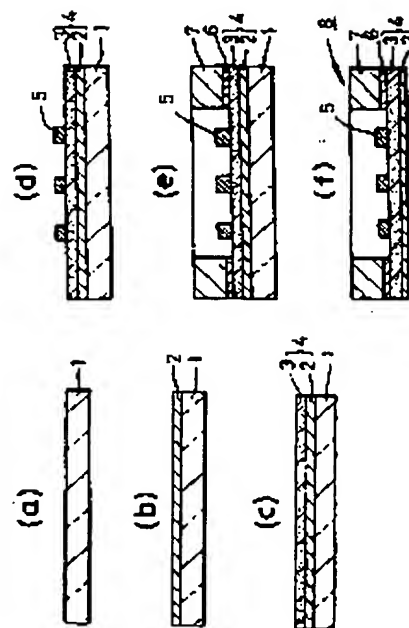
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## (54) MASK FOR SOFT X-RAY TRANSFER AND ITS PRODUCTION

## (57)Abstract:

PURPOSE: To obtain a titled mask which is strong to mechanical impact and has good flatness by constituting a support for a transfer pattern of a composite film of a polyimide film and a silicon dioxide film, and securing a support frame made of quartz glass on the silicon dioxide film.

CONSTITUTION: A polyimide film 2 and a silicon dioxide film 3 of about  $0.2\mu$  thickness are successively formed on a glass substrate 1 having about  $100\mu$  thickness and a smooth surface, thereby forming a support 4 consisting of a laminate of the films 2 and 3. A soft X-ray absorptive pattern 5 of about  $0.2\mu$  thickness consisting of Au, Pt, etc. is formed thereon. A support frame 7 made of quartz glass of about  $250\mu$  thickness subjected separately to prescribed windowing is adhered with an adhesive layer 6 on the film 3, whereafter the substrate 1 is removed from the film 2 and a mask 8 for soft X-ray transfer is obtd.



## LEGAL STATUS

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